LDO

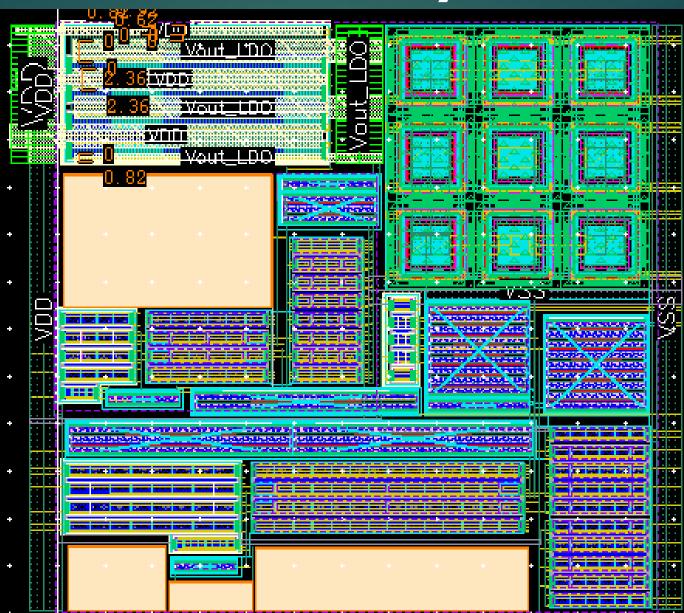
Previous Week:

- Implemented metal stacking to decrease the IR Drop in the LDO layout. Voltage drop performance improved threefold.
- Verified dynamic parameters PSRR, output noise, and transient stability using a 10ps pulse (1.8V to 0V) on VDD to check settling time.

Next:

Finishing project deliverables and documentation.

LDO - Layout



71 x 62

LDO – Results

Parameter	This Work	Schematic
Process	28nm	28nm
Layout Area (mm ²)	0.0044	N/A
Supply Voltage V_{DD} (V)	1.38-3	1.2-3
Output Voltage VOUT (V)	0.9	0.9
Load Current ILoad (mA)	55.5	55.5
Quiescent Current IQ (µA)	80	80
Line Regulation (mV/V)	0.9	0.9
Load Regulation (mV/mA)	0.032	0.002
Temperature Coefficient (ppm/°C)	6.4	6.2
PSRR (dB @1kHz)	-60.8	-60.7
Output Noise (nV/ \sqrt{Hz} @100kHz)	672	2000
Settling Time - Worst Case (μs)	0.7	_